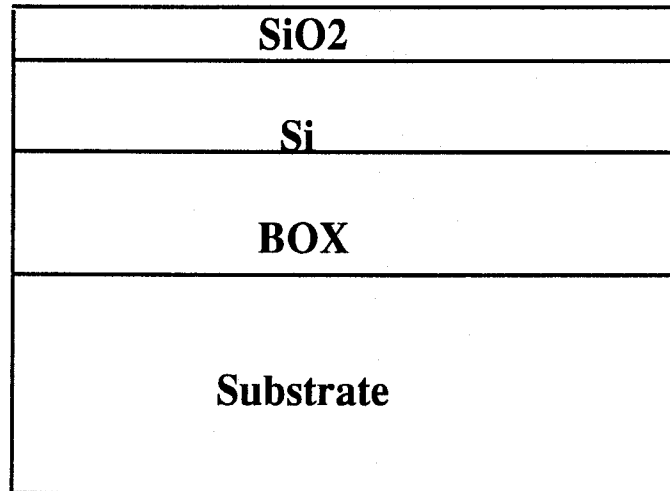


**SPECTROSCOPIC ELLIPSOMETRY OF
SILICON-ON-INSULATOR MATERIALS**

**Harold J. Hovel
IBM Corporation
Yorktown Hts, NY**

BASIC SOI STRUCTURE



Simple 3 Layer Model

SiO₂ / Si / SiO₂ / Substrate

BONDED SOI
Thick BOX

3997 SiO₂

DO127, Si Removed

1800 Si

3974 SiO₂

DO127, Si On.

4021 SiO₂

4282-1826, Si Removed

2087 Si

4085 SiO₂

4282-1286, Si On.

4014 SiO₂

U6AZJTG, Si Removed

1950 Si

4077 SiO₂

U6AZJTG, Si On.

BONDED SOI
Thin BOX

1435 SiO₂

JRD04SY, Si Removed

1545 Si

1320 SiO₂

JRD04SY, Si On.

1410 SiO₂

5GU49, Si Removed

1480 Si

1344 SiO₂

5GU49, Si On.

1417 SiO₂

E93, Si Removed

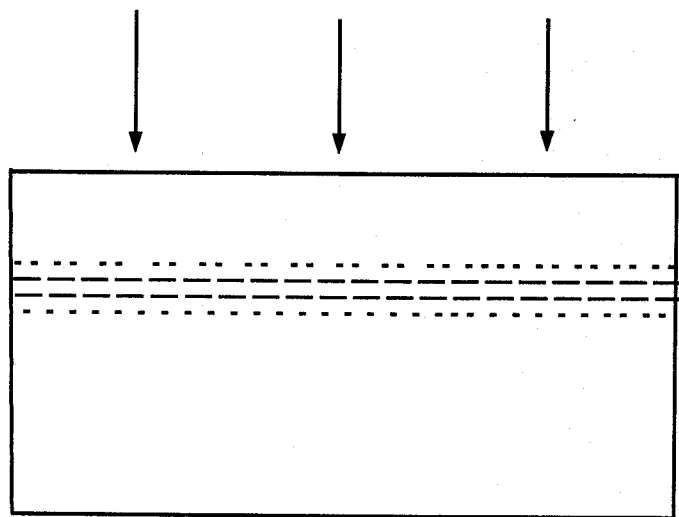
1496 Si

1266 SiO₂

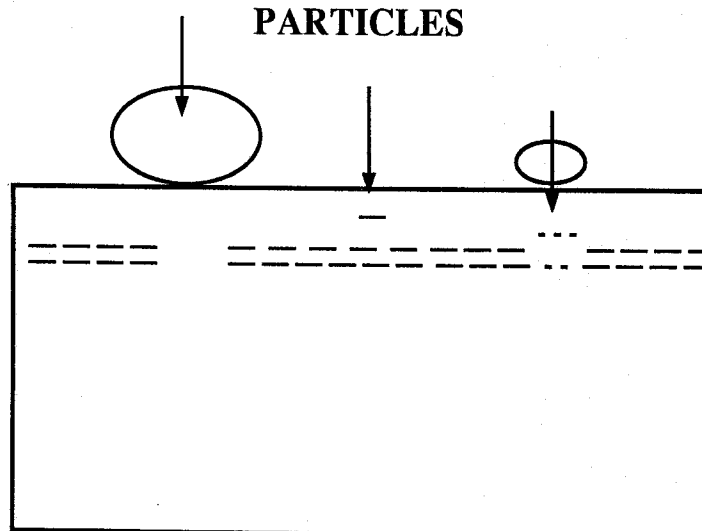
E93, Si On.

SIMOX

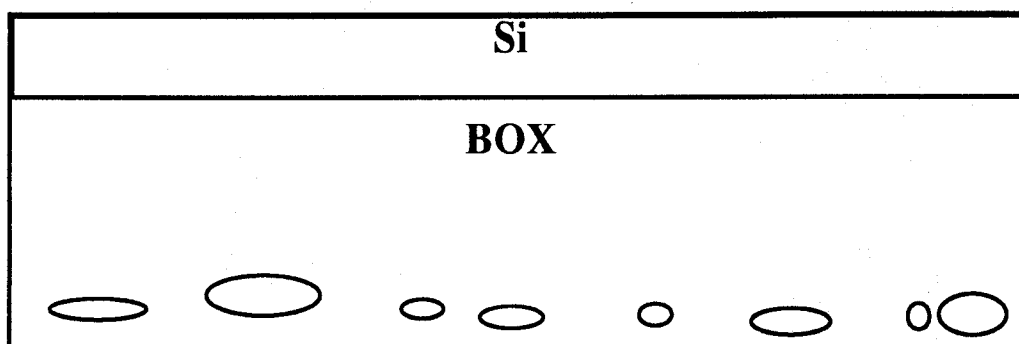
Oxygen Implant



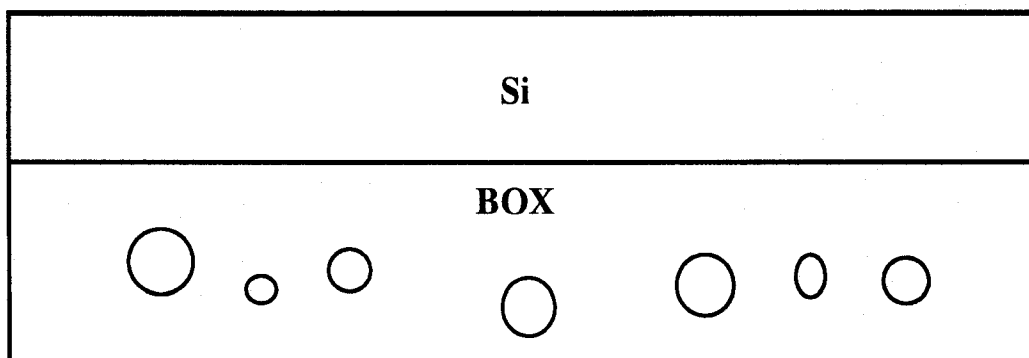
PARTICLES



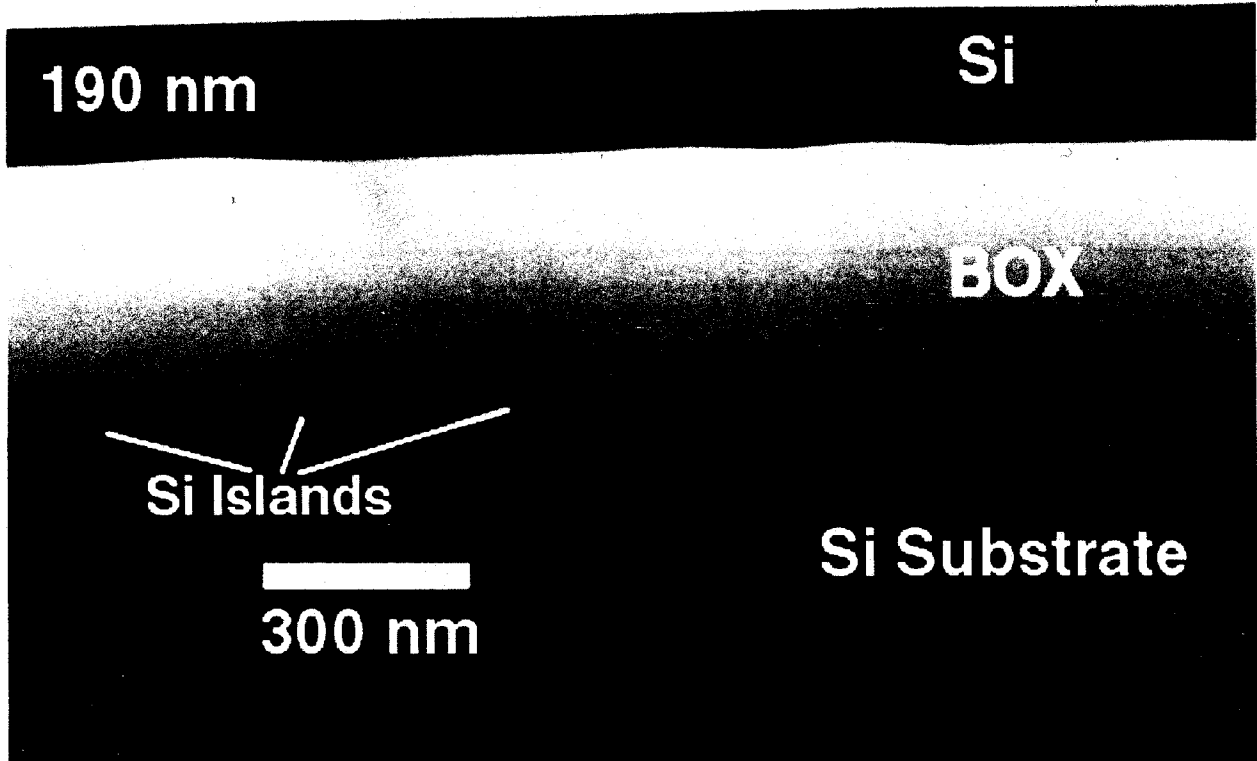
SIMOX



Si Islands In BOX
Standard Dose



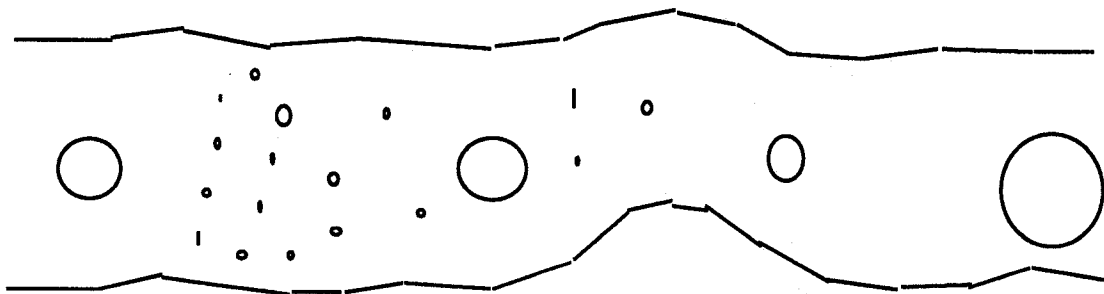
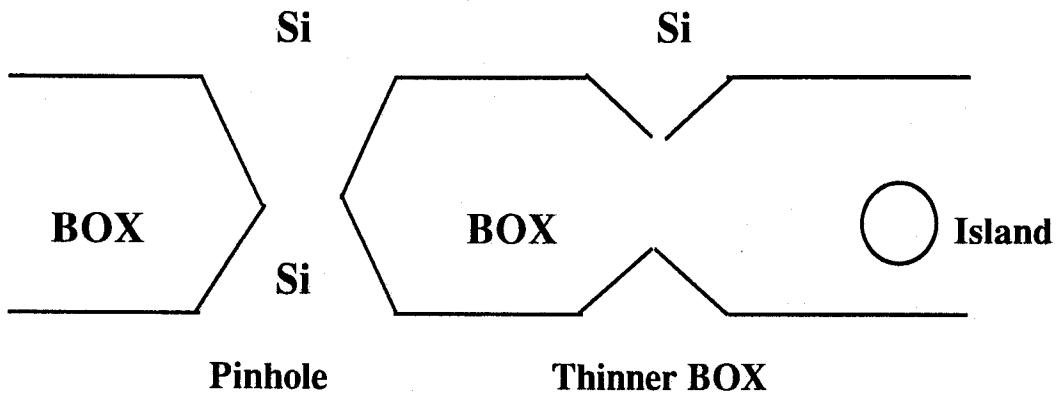
Si Islands in BOX
Low Dose





1 micron

A. Domenicucci



SIMOX BOX Abberations.

Pinholes

Thinner Regions

Rough Interfaces

Amorphous Si Clusters - Si Richness

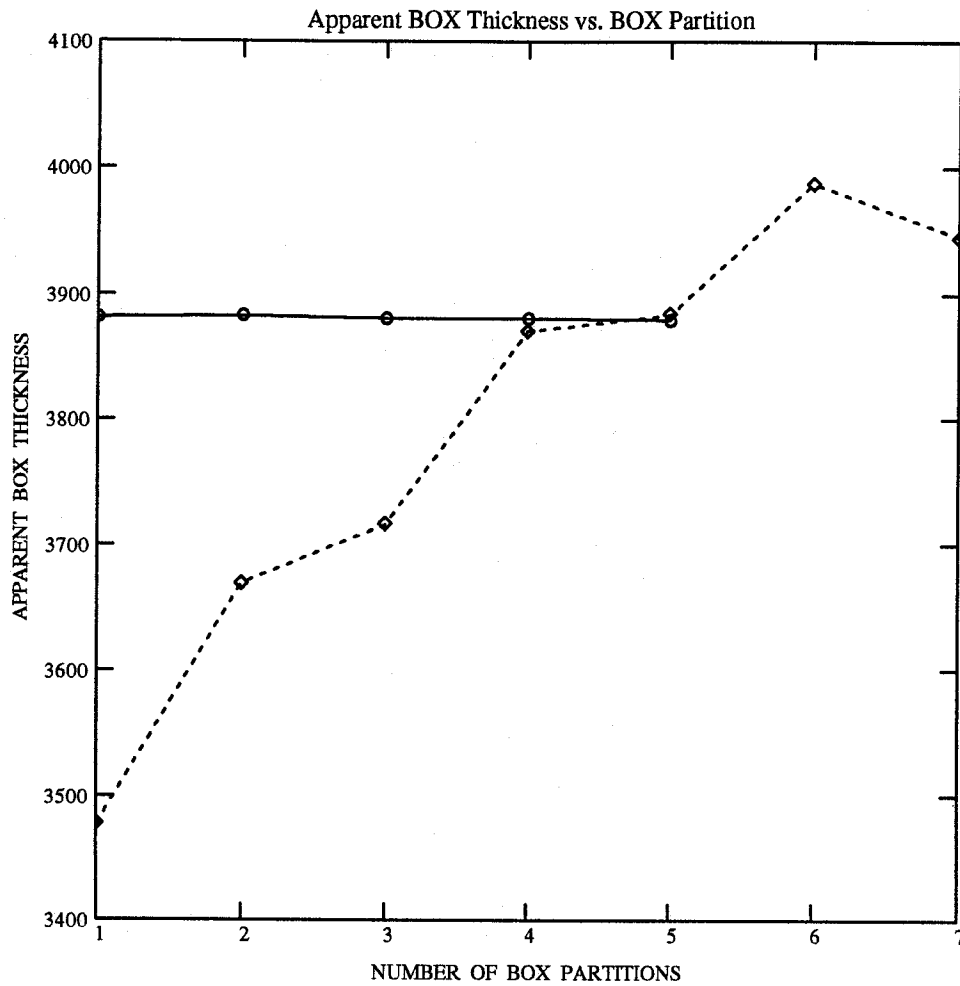
SIMOX MODELS

SiO ₂
Si
SiO ₂ + SiO
SiO ₂ + SiCr
SiO ₂ + SiO

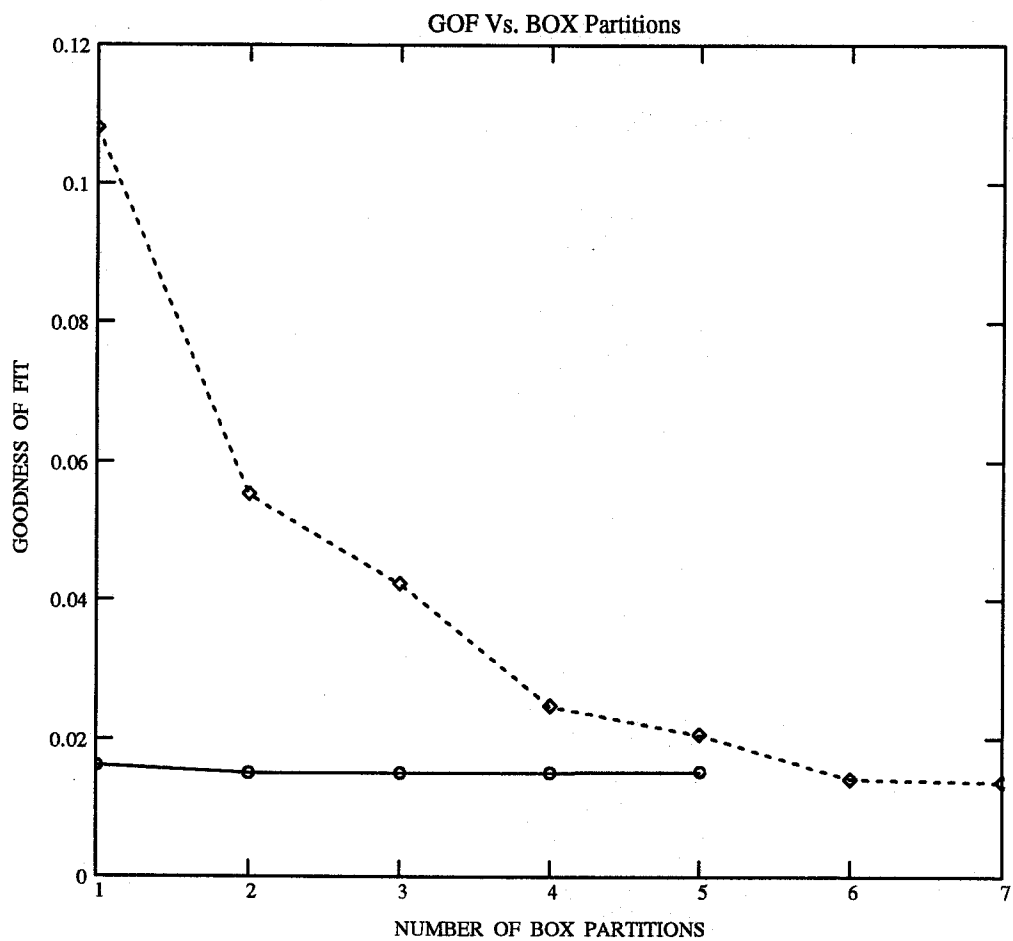
Standard Dose SIMOX

SiO ₂
Si
Si + aSi
SiO ₂ + aSi
SiO ₂ + SiCr
SiO ₂ + SiO

Low Dose SIMOX



BOX Thicknesses from Regressions After Partitioning the BOX into the Number of Layers Shown on the X Axis. Bonded SOI (solid line) and SIMOX (dotted line).



Goodness of Fit from Regressions After Partitioning the BOX into the Number of Layers Shown on the X Axis. Bonded SOI (solid line) and SIMOX (dotted line).

Standard Dose SIMOX: BOX ONLY

3656 SiO₂ + .11 SiO

1 Layer. $\sigma = .108$

3621 SiO₂ + .045 aSi

2 Layer. $\sigma = .054$

212 SiO₂ + .58 cSi

BOX = 3832

3630 SiO₂ + .042 aSi

197 SiO₂ + .57 cSi

3 Layer. $\sigma = .0399$

54 SiO₂ - .61 SiO

BOX = 3881

3353SiO₂ + .013 aSi

484 SiO₂ + .132 aSi

4 Layer. $\sigma = .021$

59 SiO₂ + .92 cSi

BOX = 4010

114 SiO₂

3117 SiO₂ + .01 aSi

568 SiO₂ + .068 aSi

189 SiO₂ + .27 cSi

5 Layer. $\sigma = .019$

19 SiO₂ + 1 cSi

BOX = 4020

127 SiO₂ - .04 SiO

**Comparison of Models for BOX Determination.
IBM 149; M503P5Y**

Standard Dose SIMOX: Full SOI.

1812 Si
3433 SiO ₂ + .17 SiO

$\sigma = .027$
BOX = 3433

1807 Si
3537 SiO ₂ + .085 SiO
287 SiO ₂ + .59 aSi

$\sigma = .019$
BOX = 3823

1818 Si
3730 SiO ₂ - .037 aSi
392 SiO ₂ + .33 cSi
114 SiO ₂ - .44 SiO

$\sigma = .013$
BOX = 4236

1818 Si
3532 SiO ₂ + .01 aSi
308 SiO ₂ + .31 cSi
68 SiO ₂ + .47 cSi
98 SiO ₂ - .48 SiO

$\sigma = .01935$
BOX = 4006

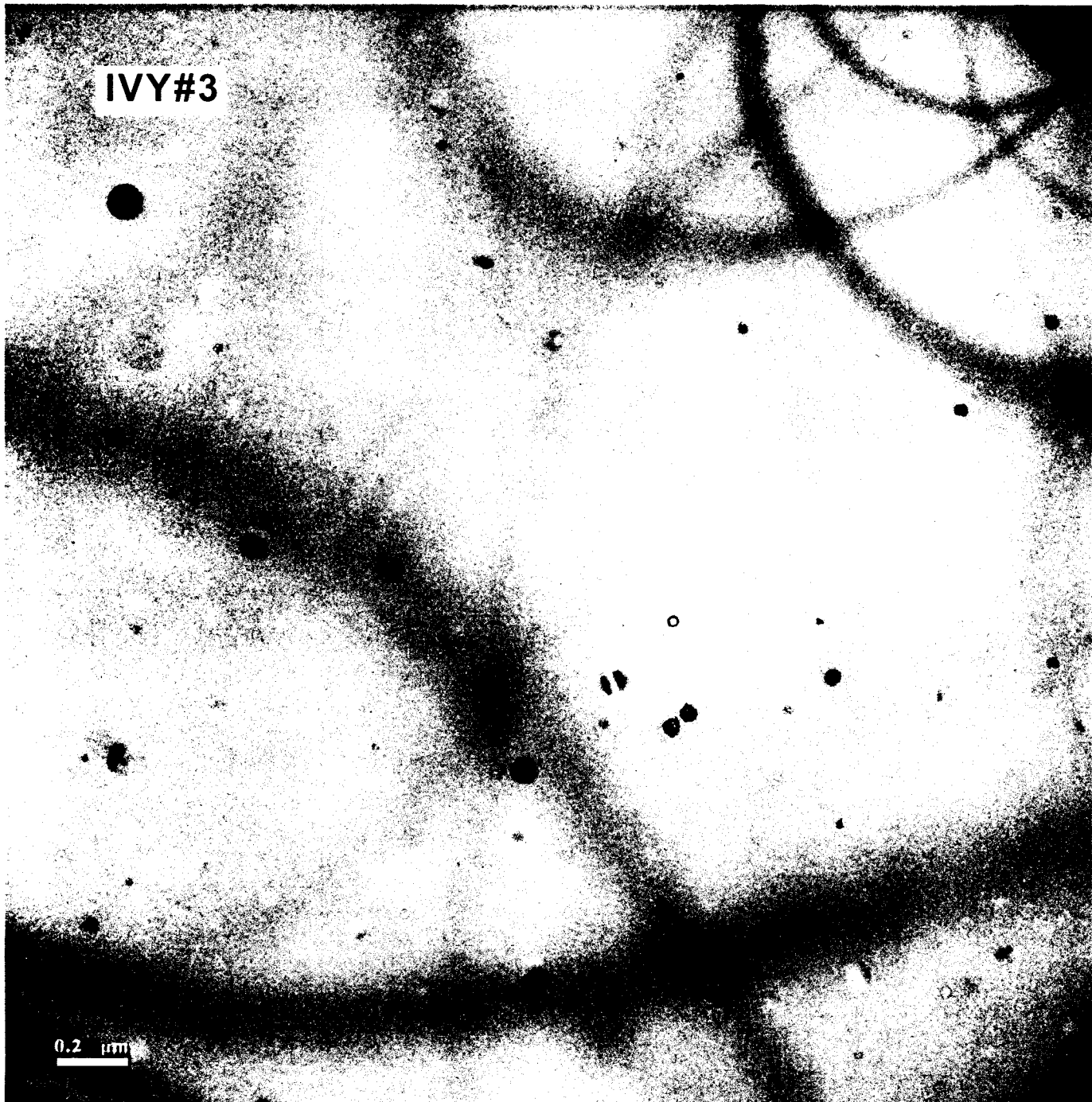
**Comparison of Models for Si and BOX Determination.
IBM 149; M503P5Y**

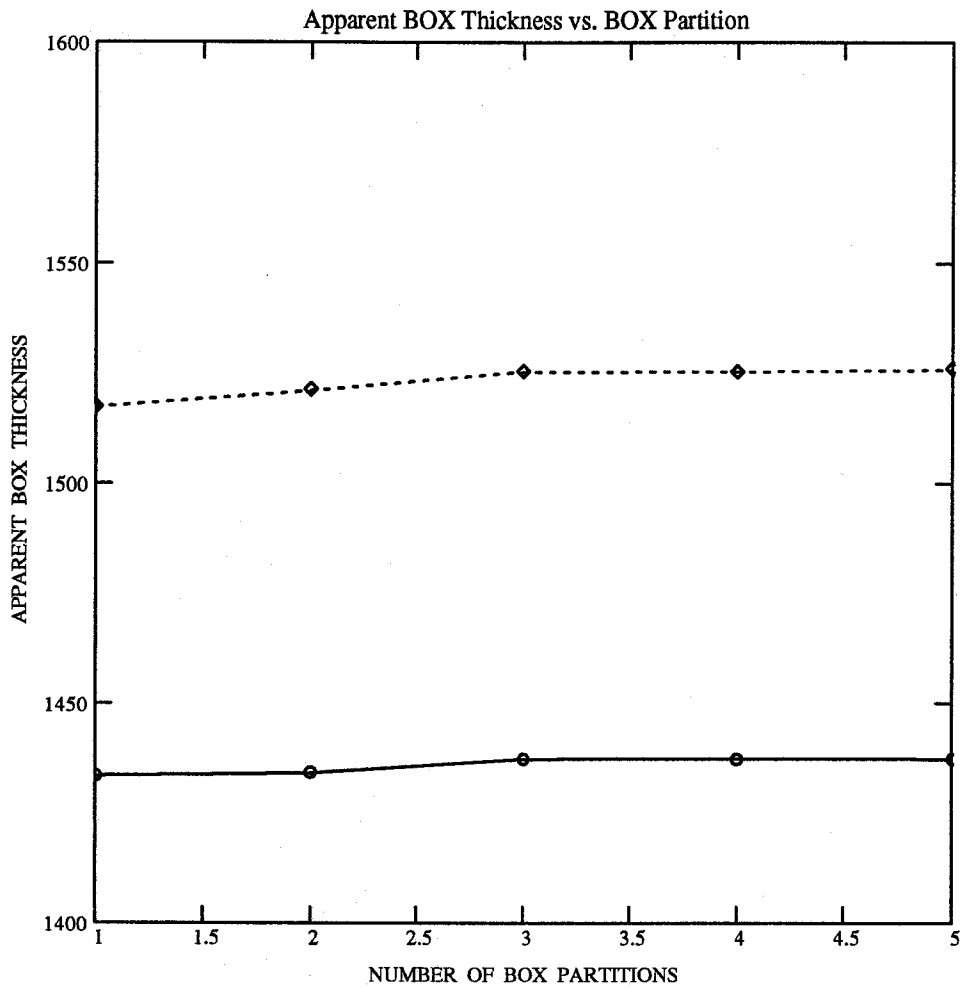


0.20 μm

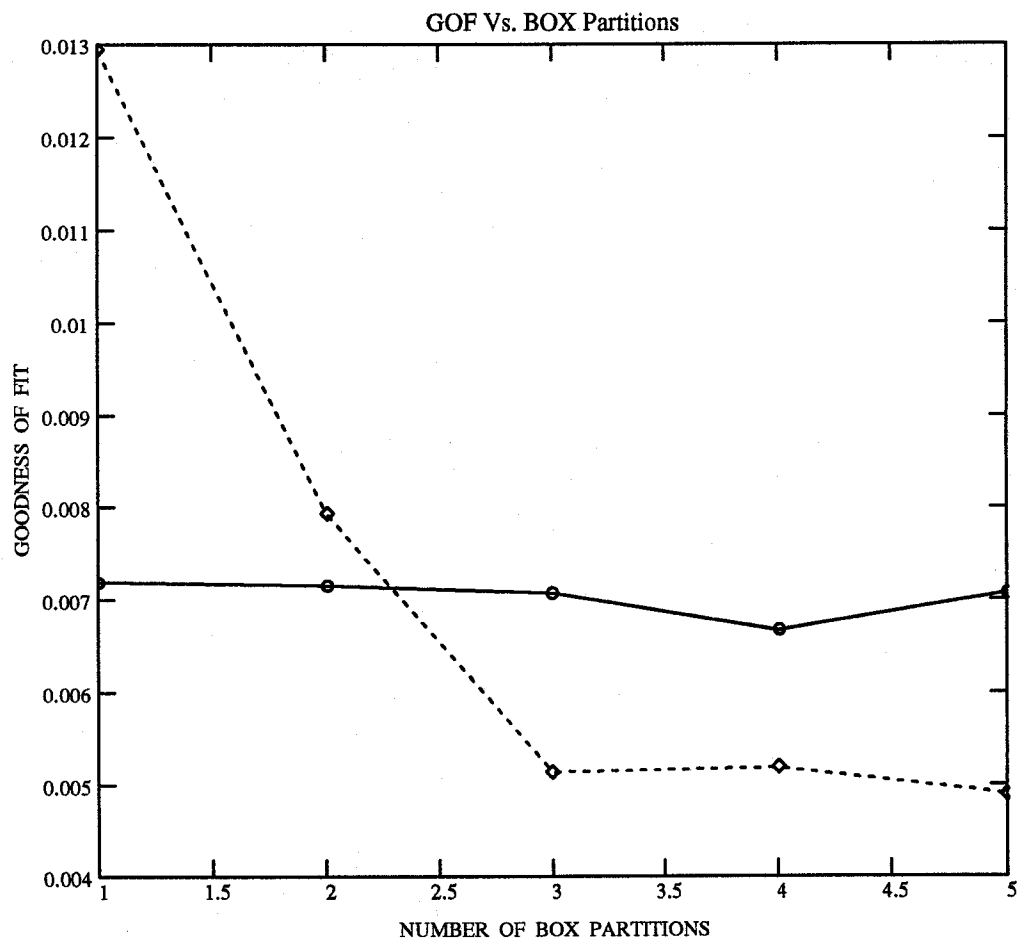
IVY#3

0.2 μm





BOX Thicknesses from Regressions After Partitioning the BOX into the Number of Layers Shown on the X Axis. Bonded SOI (solid line) and SIMOX (dotted line).



Goodness of Fit from Regressions After Partitioning the BOX into the Number of Layers Shown on the X Axis. Bonded SOI (solid line) and SIMOX (dotted line).

Low Dose SIMOX: BOX ONLY.

1517 SiO₂ + .017 cSi

**1 Layer. $\sigma = .0129$
BOX = 1517**

771 SiO₂ + .016 aSi

750 SiO₂ + .013 cSi

**2 Layers. $\sigma = .0079$
BOX = 1521**

613 SiO₂ + .0066 aSi

30 SiO₂ + .217 cSi

882 SiO₂ + .011 SiO

**3 Layers. $\sigma = .00513$
BOX = 1525**

613 SiO₂ + .0068 aSi

5 SiO₂ + .0006 cSi

30 SiO₂ + .21 cSi

877 SiO₂ + .011 SiO

**4 Layers. $\sigma = .00518$
BOX = 1525**

615 SiO₂ + .0084 aSi

4 SiO₂ - .87 aSi

56 SiO₂ + .098 cSi

5 SiO₂ + .34 cSi

845 SiO₂ + .012 SiO

**5 Layers. $\sigma = .00489$
BOX = 1526**

**Comparison of Models for Si and BOX Determination.
Low Dose ,5E17, MR13QIY**

LOW DOSE SIMOX: Full SOL. (BOX = 1526 Angs.)

12 SiO ₂
1540 Si
1438 SiO ₂

1 Layer BOX .
BOX = 1438
 $\sigma = .0151$

9 SiO ₂
1562 Si
1005 SiO ₂ + .017 aSi
353 SiO ₂ + .17 cSi

2 Layer BOX.
BOX = 1357
Si = 1562
 $\sigma = .0105$

9 SiO ₂
1561 Si
1040 SiO ₂ + .014 aSi
310 SiO ₂ + .19 cSi
7 SiO ₂ + .24 SiO

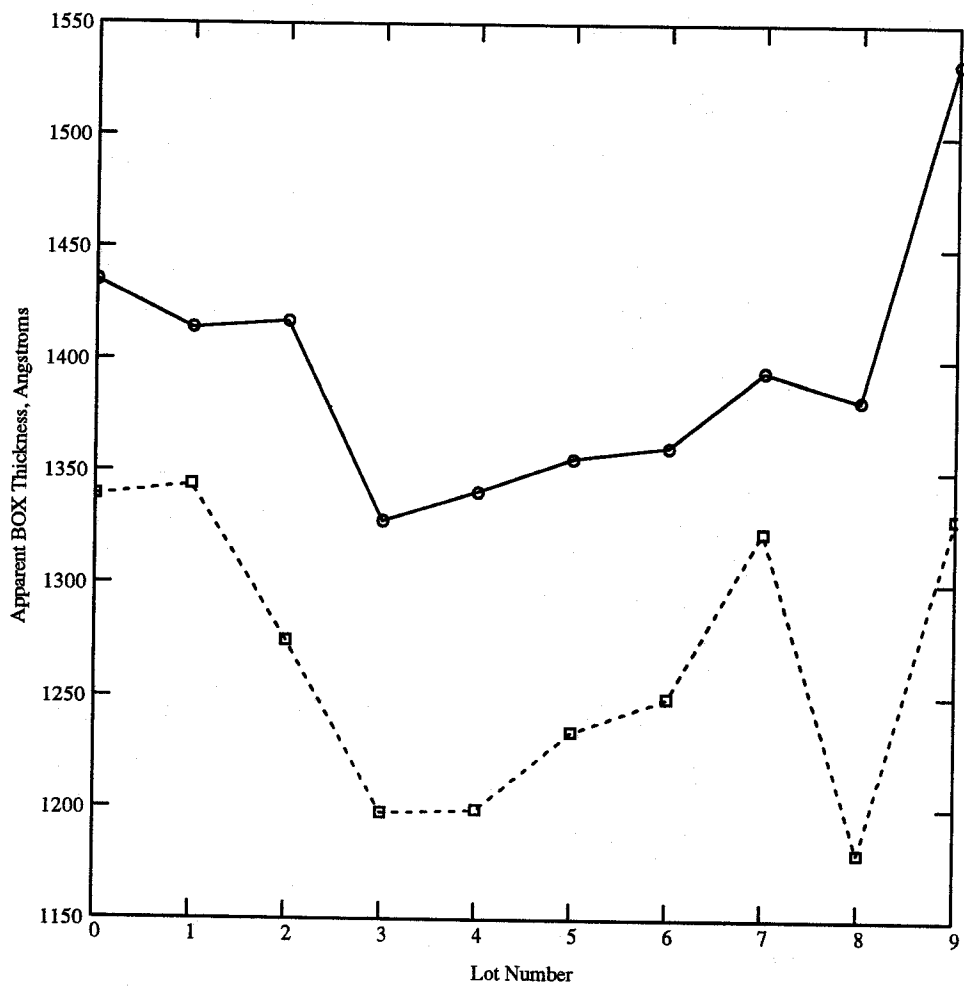
3 Layer BOX.
BOX = 1357
Si = 1561
 $\sigma = .0106$

9 SiO ₂
1562 Si
1000 SiO ₂ + .014 aSi
16 SiO ₂ + .14 cSi
310 SiO ₂ + .18 cSi
35 SiO ₂ + .13 SiO

4 Layer BOX.
BOX = 1361
Si = 1562
 $\sigma = .0105$

Comparison of Models for Low Dose SIMOX. MR13QIY

Difference Between Buried Oxide Measured with the Si Layer Intact or Removed.



SUMMARY

- 1. Bonded SOI: No BOX Partitioning is Needed.**
- 2. For SIMOX, accurate BOX measurements require partitioning the BOX into 3 sections (thin BOX material) or 4 sections (thick BOX material).**
- 3. The need for BOX partitioning is a result of non-uniformities, especially Si islands, in the SIMOX buried oxide.**
- 4. For thick BOX structures, bonded and SIMOX, the error in measuring the BOX thickness with the Si intact is small.**
- 5. For thin BOX structures, bonded and SIMOX, there is considerable error in measuring the BOX with the Si layer in place.**